# Single Crystal Diamond NEMS Switch

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# 待機電力消費---半導体スイッチ

機器が非使用状態、若しくは何らかの入力(命令指示)待ちの時に定常的に消費している電力

#### 待機時消費電力量の占める割合



▶普段の生活のエネルギー消費を減らす必要!

✓ナノマシンスイチ:省エネルギー技術(ゼロ)として期待。

# **MEMS switch:** Merits



**MEMS** switch

#### Advantages over semiconductor devices

But, poor reliability due to

**OFF** state

Surface stiction (i)(ii) Mechanical abrasion

**ON** state

#### **Diamond MEMS: route toward high reliability and high performance**



# **Challenges and Strategies in Diamond MEMS**

What process....?

What device concept.....?

#### **Difficulties**

Batch fabrication of single crystal diamond MEMS structures.
 Lack of device concepts compatible with the fabrication process.

#### Aims

Establish unique process for diamond MEMS structures.
 Develop high-performance diamond MEMS/NEMS devices.
 Create novel device concepts.

#### **Strategies**

No direct deposition of diamond on sacrificial layers.
Diamond-on-Diamond lateral device concept.

# **Diamond growth**



#### MPCVD





#### Parameters:

Gas:  $H_2$  (500 sccm),  $CH_4$  (0.4 sccm) RF Power: 400 W Pressure: 80 Torr Sub. Tem: 900-950°C [B]:1000 ppm  $10^{20}$ cm<sup>-3</sup> Substrate: Ib (100)---100 ppm nitrogen Thickness: 0.1-0.5µm

## **Batch production of micro-scale M/NEMS structures**





*M. Y. Liao, et al, Advanced Materials* 22, 5393 (2010)









M. Y. Liao, et al, J. Micromech. Mircoeng. 20, 085002 (2010)



#### **Quality of the MEMS/NEMS structure**



## **Nanoindentation of MEMS structures**



Young's modulus: 800±200 GPa (Calibrated by Si cantilever)

M. Y. Liao, et al, J. Micromech. Mircoeng. 20, 085002 (2010)

## **Nanoelectromechanical switch: 2-terminal**



## **Nanoelectromechanical switch: 3-terminal**



## **3-T NEMS switch: Reliability**



100Hz AC V<sub>G</sub>



#### **High temperature operation**



## **Modeling and simulation of NEMS switch**

$$-\nabla \cdot (\varepsilon \nabla \mathbf{V}) = \mathbf{0}$$

Potential in the air around the beam

$$\mathbf{F}_{es} = -\frac{1}{2} (\mathbf{E} \cdot \mathbf{D}) \mathbf{n} + (\mathbf{n} \cdot \mathbf{E}) \mathbf{D}^{\mathrm{T}}$$

F<sub>es</sub>: Electrostatic force density of the beam E: electric field, D: displacement vector

$$V_{\text{pull-in}} = \sqrt{\frac{4c_1 B}{\epsilon_0 L^4 c_2^2 (1 + c_3 \frac{g}{W})}}$$

Pull-in voltage: defined as the beam contact to the gate. L: length, W: width, t: thickness

 $B=E_0t^3g^3$ 



#### **Modeling and simulation of NEMS switch**



## **Comparison between experiment and simulation:**



# **Applications of diamond M/NEMS** Switch: H<sup>4</sup>





#### For the first time

Single-crystal diamond NEMS switch was fabricated.

> Batch production of SCD MEMS/NEMS structures were developed.

The diamond NEMS switches exhibit high performance.
 (1) High controllability .
 (2) High reproducibility.
 (3) Good reliability.

Modeling and simulation were made and were consistent with experiments